

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

1-6. (cancelled).

7. (Currently amended) Method of controlling the gas flow within a device (1) for wet treating a substrate (W), the device comprising a liquid collector and at least two exhaust levels for separately collecting gas from the interior of the liquid collector, characterized in ~~selectively~~ individually generating different gas flow conditions in at least two of said exhaust levels.

8. (original) Method according to claim 7 wherein the different gas flow conditions are selected in a way to achieve substantially the same gas pressure adjacent to the rotating substrate above and below said substrate.